## Abstract

5

10

15

A method for low-pressure spray cleaning and residual contaminant analysis of components is described which includes providing a receiver tank (B1) filled with flushing medium, pressurizing the receiver tank (B1) with compressed air on the inlet side, conducting the pressurized flushing medium to a spray lance (S1), spray cleaning a component by spraying the flushing medium from the spray lance (S1), collecting the particle-containing flushing medium after the spray cleaning in a collection tank (B2), providing an inline analysis filter (F2) positioned on an outflow side of the collection tank (B2) in such a way that particle-containing flushing medium flows through it, filtering the particles out of the flushing medium using the analysis filter (F2) and finally analyzing the residual contamination filtered out by the analysis filter. A low-pressure spray module suitable for use with this method is also described (Figure 1).